

ABSTRACT OF THE DISCLOSURE

There is provided an electron beam exposure technique which permits optical adjustment in an electron optics system using a doublet lens necessary  
5 for large field projection.

Electron beam exposure equipment having a part forming one image by at least two electromagnetic lenses, has means measuring the position of an electron beam near an image plane with changing excitation of at  
10 least two lenses at the same time; and control means feeding back the measured result to aligners or the intensity of the lenses.